



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Application Serial No. .... 09/298,160  
Filing Date ..... April 22, 1999  
Inventor ..... Dan G. Custer et al.  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 1746  
Examiner ..... A. Olsen  
Attorney's Docket No. .... MI22-1172  
Title: Polishing Systems, Methods of Polishing Substrates, and Methods of  
Preparing Liquids for Semiconductor Fabrication Processes

**PRELIMINARY AMENDMENT TO ACCOMPANY AN RCE FILING**  
**In Response to the December 15, 2000 Final Office Action**

To: Box RCE  
Assistant Commissioner for Patents  
Washington, D.C. 20231

From: Bernard Berman (Tel. 509-624-4276; Fax 509-838-3424)  
Wells, St. John, Roberts, Gregory & Matkin P.S.  
601 W. First Avenue, Suite 1300  
Spokane, WA 99201-3828

Sir:

Responsive to the Final Office Action dated December

Applicant submits this Preliminary Amendment with an RCE filing and respectfully requests reconsideration of the above-references application in view of the amendments and remarks hereinbelow.

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